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APR 29 2002

PATENT

TECHNOLOGY CENTER 2800

Customer No. 22,852

Attorney Dock t No. 08038.0027

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)
Hikaru YOSHITAKA	) Group Art Unit: 2812
Serial No.: 09/658,861	) Examiner: Nguyen, H.
Filed: September 8, 2000	) VIA FACSIMILE @ (703) 308-7722
For: SEMICONDUCTOR DEVICE AND METHOD OF MANUFACTURING THE SAME	) ) )

Assistant Commissioner for Patents Washington, DC 20231

Sir:

## SUPPLEMENTAL AMENDMENT

In reply to a telephone conference with Examiner Nguyen on April 26, 2002, Applicant hereby further amends the application as follows:

## IN THE CLAIMS:

Please amend claim 4 as follows:

4. (Twice Amended) A method of manufacturing a semiconductor device, said method comprising the steps of:

forming a wiring layer on a semiconductor substrate having an active region formed thereon;

forming a first insulating layer containing carbon on said wiring layer;

BI

LAW OFFICEA

NECAN, HENDERSON,
FARABOW, CARRETT,
& DUNNER, L.L.P.
1300 I STREET, N. W.
ASMINGTON, DC 2000B
202-408-4000